

HV-HR CMOS Detectors for FCC- ee (and also hh)

ITK

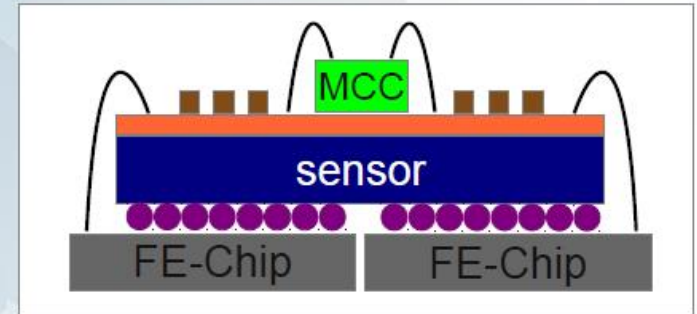
General considerations for Si tracking at FCC

- FCC-ee
 - Cost of present (planar pixels):
 - Sensor 25-40 euro/cm²
 - FE : 14 euro/cm²
 - Bump-bonding : 40-45 euro/cm²
 - Low amount of material $\ll 1\%$ X0 per layer
 - Granularity : few μ pitch
- FCC-hh
 - Radiation hardness
 - Low power (for cooling)

Silicon Hybrid Detectors

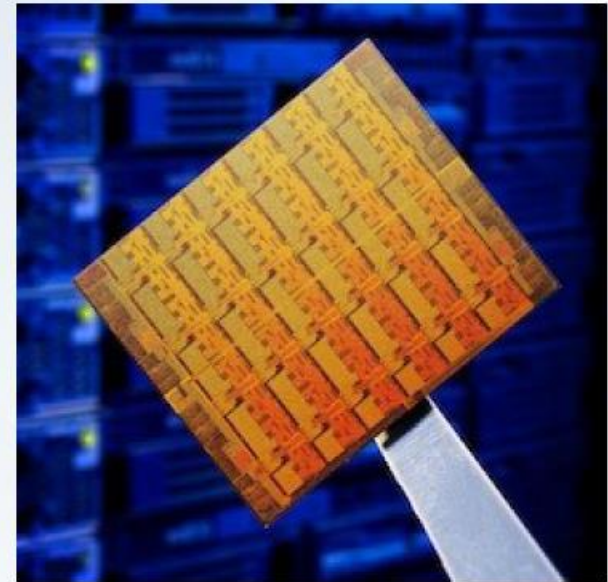
Features

- high signal and high noise
 - complex compound
 - bump bonding
 - wire wrapping
 - custom-made sensor
 - lots of material (radiation lengths!)
- expensive (e.g. ATLAS II pixel HW: 16 mill.CHF for $\sim 5\text{m}^2$)
- scalability problem (e.g. Future experiments at FCC)
- miniaturization problem $>10^8/\text{m}^2$ bump bonds?
- quality assurance problem



CMOS Features

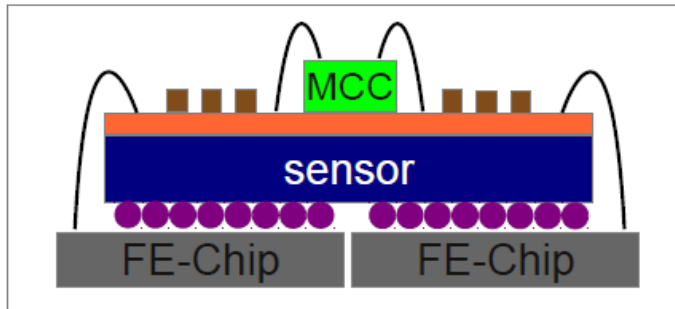
- minimum pixel size 10-20 feature size
→ **5 μ m possible!!!**
- low power (CMOS)
- low noise compared to hybrids
- compact VLSI design
- standard process
- cheap



Hybrid versus Monolithic

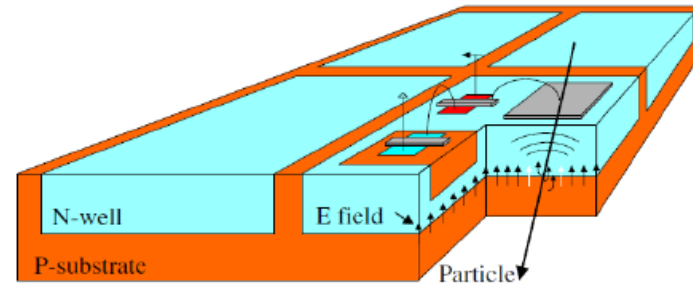
Hybrid design

- high signal
- high noise
- lot of material
- many interconnections
- minimum pixel size limited by bump bonds
- expensive (connections!)
- complex production



Monolithic design

- low signal can be increased!
- low noise
- 50 μm thickness possible → Mu3e
- only few connections
- minimum pixel size only limited by features size ~4x4 μm^2 for 180nm
- cheap CMOS process
- easier (faster) to construct?



CCPD – Capacitively Coupled Pixel Detectors

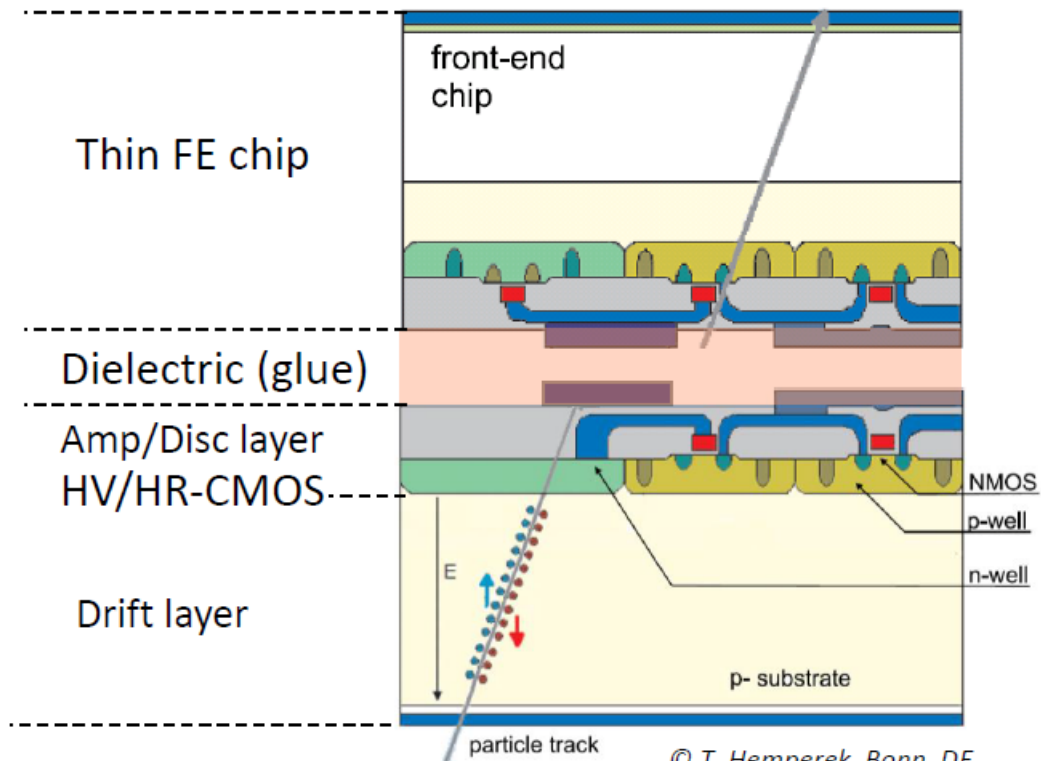
New generation of Pixel detectors under development for the ATLAS Pixel detector at the HL-LHC

- Passive hybrid detectors use “resistive” coupling between sensor and R/O chip
- HV-CMOS detector use a High Voltage chip technology to make sensor and amplifier which is then coupled to the “usual” front-end chip...

- through a dielectric...

Why capacitive?

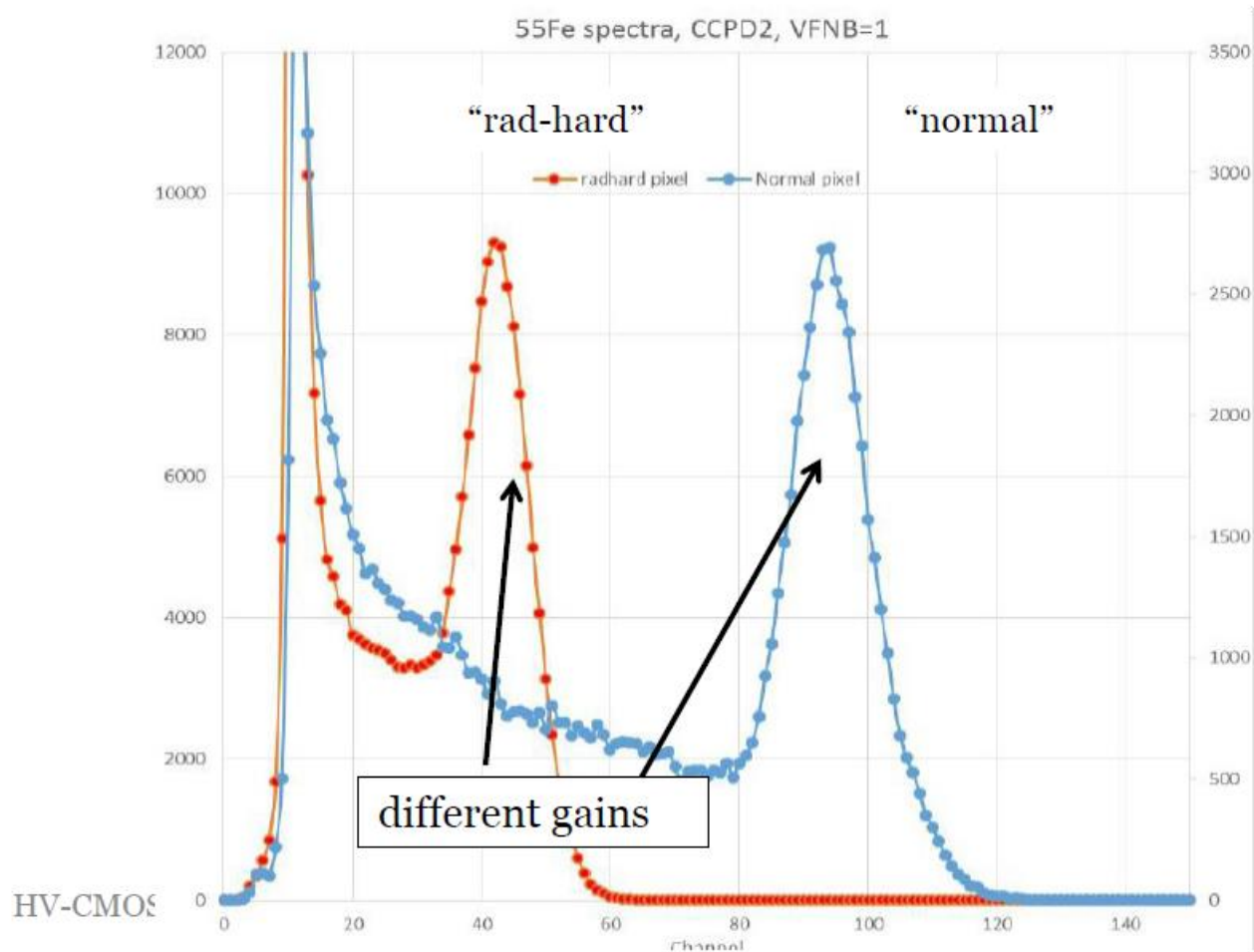
- Passive sensors need diode biasing from amplifier other than for collecting charge: AC coupling is (almost) not an option.
- **Capacitive coupling it might be cheaper:** glue and alignment looks easier.



HV2FEI4_V2

- Few pixel flavors with enhanced rad-hardness: guard rings, circular transistors... (different pixel types lead to different gains -expected-).

^{55}Fe spectra, unirradiated



Capacitance uniformity

- Between pixels, from an assembly to another: $\sim 10\%$ \rightarrow thickness uniformity
- Most critical for analog coupling (no discriminator in the HV/HR-CMOS)
- RD-53 chips will have $50\mu\text{m}$ pitch, but also versions for very small pixels: $25\mu\text{m}$ pitches are considered
- X-Y alignment: better than few μm (cross talk / signal loss)

Glue requirements

- Low viscosity: $0.1 \div 0.5$ Pas
- Radiation hard: epoxy
- Not degassing
- Low temperature curing, investigating UV/Temp curing glues
- Minimum thickness of glue to give for full adhesion (usual specs are 1-2 mil, but we want less!)

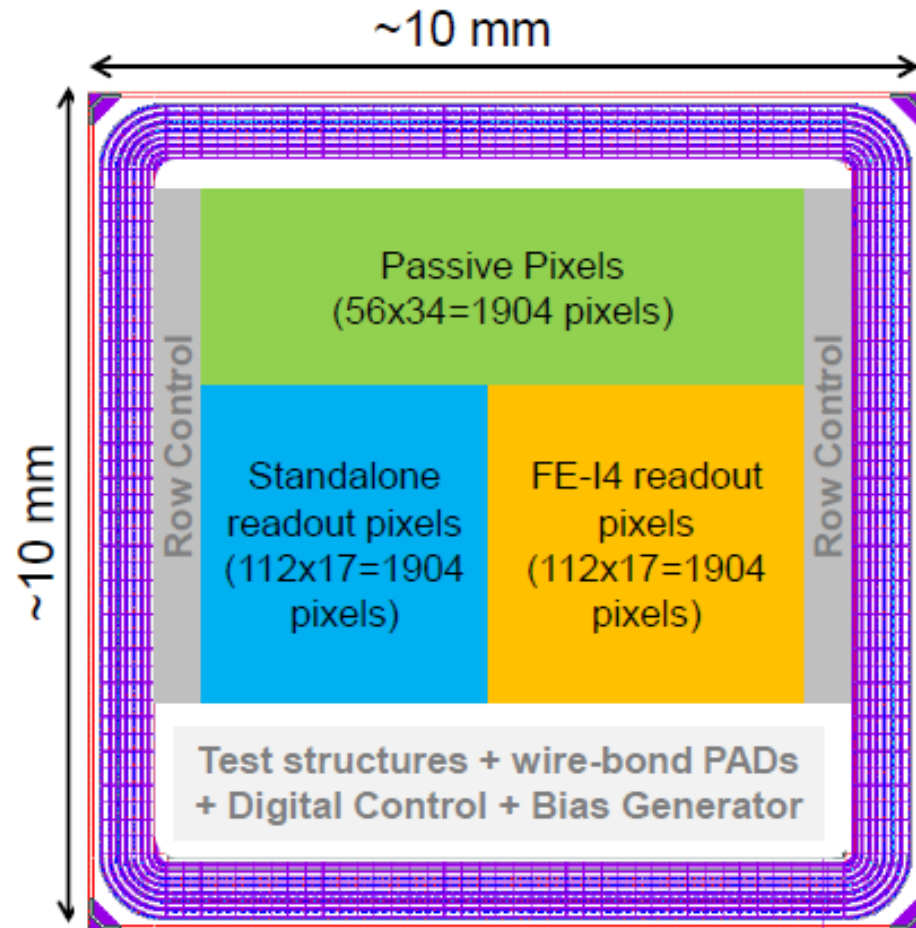
For chip-to-wafer and wafer to wafer TVS are needed on one or both facing chips

- For the moment we are looking at chip-to-chip processes

Irfu activities

- Participation to the design of a 150 nm Lfoundry demonstrator chip (in HL-LHC context)
- Interest to start R&D on the mechanical aspects of capacitive coupling
- Expertise developed will be useful for FCC-ee
- Monolithic pixels (HV-MAPS) best choice for FCC-ee, given low expected occupancy

- ❑ Process: **LFoundry 150nm HV-CMOS**
- ❑ Bonn, CPPM, IRFU collaboration
- ❑ Based on 2 previous prototypes (pixel electronics **inside/outside** detection diode) designed by Bonn&CPPM
- ❑ Passive, digital, and analog output pixels
- ❑ Pixel properties:
 - Pitch: **250µm x 50µm**
 - Peaking time: **~20 ns**
 - Power dissipation: **~20µW** (analog)
 - Detector capacitance: 200-400fF
 - Noise : **100-250e-**
- ❑ Re-use of already validated peripheral circuits
- ❑ Submission foreseen for **September 2015**



Demonstrator layout